## Amendments to the claims are as follows:

(Currently Amended) A thin-film magnetic head comprising:
 a lower core layer formed so as to extend in a height direction from a surface opposing a recording medium;

a magnetic layer connected to the lower core layer directly or indirectly at a position spaced from <u>anthe</u> opposing surface in the height direction by a predetermined distance; and

a coil layer toroidally winding around the magnetic layer,
wherein the toroidal coil layer is connected to a plurality of first
coil pieces formed between the lower core layer and the magnetic layer and a
plurality of second coil pieces formed on the magnetic layer, and

wherein the upper surfaces of the first coil pieces are covered with an insulating layer other than connection surfaces to the second coil pieces, the connection surfaces of the first coil pieces being raised upward and exposed from the upper surface of the insulating layer so that the second coil pieces are formed in contact with the connection surfaces of the first coil pieces.

 (Currently Amended) A head according to Claim 1, further comprising a raised layer provided on the lower core layer at a position spaced in a track width direction from <u>athe</u> center of the lower core layer in <u>athe</u> track width direction,

wherein part of the first coil pieces is mounted on the raised layer, part of the upper surfaces of the first coil pieces being exposed from the upper surface of the insulating layer at athe position on that the first coil pieces mount, so that the exposed surface becomes the connecting surface.

3. (Currently Amended) A head according to Claim 2, wherein <u>anthe</u> upper surface of the raised layer is a flattening surface, and at least part of the first coil pieces mounted on the flattening surface becomes the connecting surface.

- 4. (Original) A head according to Claim 3, wherein the first coil pieces are formed partway the flattening surface.
- 5. (Currently Amended) A head according to Claim 2, wherein <u>anthe</u> upper surface of the raised layer is a curved surface, and part of the first coil pieces mounted on the curved surface becomes the connecting surface.
- 6. (Original) A head according to Claim 5, wherein the first coil pieces are formed partway the curved surface.
- 7. (Original) A head according to Claim 1, wherein the upper surface of the insulating layer and the connection surfaces of the first coil pieces are an identical flattening surface.
- 8. (Original) A head according to Claim 2, wherein the raised layer intersects under a plurality of the first coil pieces.
- 9. (Original) A head according to Claim 2, wherein the raised layer is arranged under each of the first coil pieces.
- 10. (Currently Amended) A head according to Claim 1, wherein on the lower core layer, a lower magnetic polar layer, a gap layer, and an upper magnetic polar layer, which is the magnetic layer, are deposited in that order from beneath so as to form a deposited structure, and a track width Tw is

determined by <u>athe</u> width of the deposited structure on the opposing surface in a track width direction.

- 11. (Original) A head according to Claim 1, wherein on the lower core layer, at least a lower magnetic polar layer, a gap layer formed of a non-magnetic metallic material, and an upper magnetic polar layer are plated in that order from beneath so as to form a magnetic-polar tip layer with a track width Tw defined by a width of an end face adjacent to an opposing surface to a recording medium in a track width direction, and on the magnetic-polar tip layer, the magnetic layer is deposited.
- 12. (Currently Amended) A head according to Claim 11, wherein athe saturated magnetic induction density of the magnetic layer is lower than that of the upper magnetic polar layer.
- 13. (Currently Amended) A head according to Claim 1, wherein athe length of the second coil pieces in a first direction perpendicular to athe flowing direction of an electric current is larger than that of the first coil pieces in the first direction.
- 14. (Currently Amended) A head according to Claim 1, wherein athe film thickness of the second coil pieces is larger than that of the first coil pieces.
- 15. (Currently Amended) A manufacturing method of a thin film magnetic head comprising: the steps-of:
- (a) forming a lower core layer so as to extend in a height direction from a surface opposing a recording medium;

- (b) forming a raised layer on the lower core layer at a position spaced in a track width direction from <u>athe</u> center of the lower core layer in the track width direction,
- (c) forming a plurality of first coil pieces ranging from on the lower core layer to on the raised layer with separations in <u>athe</u> height direction;
- (d) forming a coil insulating layer between the first coil pieces and on the first coil pieces;
- (f) scraping <u>an</u>the upper surface of the coil insulating layer so as to form a flattening surface while exposing part of the first coil pieces formed on <u>an</u>the upper surface of the raised layer from the upper surface of the coil insulating layer; and
- (g) forming a magnetic layer on the coil insulating layer, and then forming a plurality of the second coil pieces on the magnetic layer while forming a toroidal layer composed of the first coil pieces and the second coil pieces by directly bringing an end portion of the second coil pieces into contact with the exposure surface formed on the first coil pieces.
- 16. (Currently Amended) A method according to Claim 15, wherein in the step (b), the upper surface of the raised layer is formed to be the flattening surface and in the step (f), part of the first coil pieces mounted on the flattening surface is polished to be the exposure surface.
- 17. (Currently Amended) A method according to Claim 16, wherein in the step (b), the first coil pieces are formed partway the flattening surface.
- 18. (Currently Amended) A method according to Claim 15, wherein in the step (b), the upper surface of the raised layer is formed to be a curved surface and in the step (f), part of the first coil pieces mounted on the curved surface is polished to be the exposure surface.

- 19. (Currently Amended) A method according to Claim 18, wherein in the step (b), the first coil pieces are formed partway the curved surface.
- 20. (Currently Amended) A method according to Claim 15, wherein in the step (f), the upper surface of the coil insulating layer and the exposure surface formed in the first coil pieces are formed to be the same flattening surface.
- 21. (Currently Amended) A method according to Claim 20, wherein in the step (f), the insulating layer and the exposure surface are formed to be the same flattening surface by CMP.
- 22. (Currently Amended) A method according to Claim 15, wherein in the step (c), the raised layer intersects under a plurality of the first coil pieces and in the step (b), the raised layer is formed in a band shape.
- 23. (Currently Amended) A method according to Claim 15, wherein in the-step (c), the raised layer is formed under each of the first coil pieces and in the-step (b), the raised layer is decoupled.